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FILING RECEIPT



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Do-Haing Lee,**Domestic Priority data as claimed by applicant**

This application is a DIV of 10/010,548 11/08/2001

Foreign Applications

REPUBLIC OF KOREA 2000-69660 11/22/2000

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Early Publication Request: No

**** SMALL ENTITY ******Title**

Method of etching semiconductor device using neutral beam and apparatus for etching the same

Preliminary Class